Congratulations to the 30 Newly Elected IEEE Electron Devices Society Fellows

Effective January 1, 2018

Pamela Ann Abshire, Silver Spring, MD, USA for contributions to CMOS biosensors

Timothy Boykin, University of Alabama Huntsville, AL, USA for contributions to atomistic models for semiconductor device simulation

Jeffrey Calame, Annapolis, MD, USA

for contributions to high-power microwave and millimeter-wave amplifiers enabled by composite dielectric materials

Kun-yung Chang, Los Altos Hills, CA, USA for contributions to transceivers for high-performance networking and high-density memories

Kuan-neng Chen, National Chiao Tung Univeristy Hsinchu, Taiwan for contributions to 3D integrated circuit and packaging technologies

Akira Fujiwara, NTT Basic Research Laboratories Atsugi, Japan for contributions to silicon single-electron devices

Michel Houssa, University of Leuven Leuven, Belgium for contributions to materials characterization for advanced MOSFETs

Jaroslav Hynecek, Allen, TX, USA for contributions to solid-state image sensors

Thomas Kazior, Raytheon: Radio Frequency Components Andover, MA, USA for leadership in microwave and millimeter wave compound semiconductor technology and heterogeneous integration with silicon

Michael Krames, Philips Lumileds Lighting Company San Jose, CA, USA for leadership in GaN-based light-emitting device physics and its commercialization

Isaac Lagnado, San Diego, CA, USA for leadership in the development of silicon-on-sapphire technology

Xiaobing Luo, Huazhong University of Science & Technology Wuhan, China for contributions to packaging of optoelectronic devices

Chee Wee Liu, National Taiwan University Taipei, Taiwan for contributions to high-mobility Ge and SiGe MOSFETs

Ming Liu, Institute of Microelectronics of Chinese Academy of Sciences Beijing, China for contributions to the development of resistive non-volatile memories

Wei Lu, University of Michigan Ann Arbor, MI, USA for contributions to development of neuromorphic systems

Zhenqiang Ma, University of Wisconsin-Madison Madison, WI, USA

for contributions to flexible and biodegradable microwave electronics

Saibal Mukhopadhyay, Georgia Institue of Technology Atlanta, GA, USA for contributions to energy-efficient and robust computing systems design

Hideo Ohno, Tohoku University Sendai, Japan for contributions to materials and device design for spintronics

Hidetoshi Onodera, Kyoto University Kyoto, Japan for contributions to variation-aware design and analysis of integrated circuits

Philippe Paillet, University of Montpellier-CEA Paris, France for contributions to the understanding of radiation effects in electronics

Joseph Pawlowski, Micron Technology, Inc. Boise, ID, USA for contributions to memory system interfaces

Seiji Samukawa, Tohoku University Sendai, Japan for contributions to damage-free plasma processing for nanodevice manufacturing

Riichiro Shirota, National Chao-Tung University Hsinchu, Taiwan for contributions to the development of NAND flash memory

Gregory Snider, University of Notre Dame Notre Dame, IN, USA for contributions to single electron based computing technology

Shuji Tanaka, Tohoku University Sendai, Japan for contributions to micro-electromechanical systems for acoustic wave devices, physical sensors, and power generation

Victor Veliadis, PowerAmerica Raleigh, NC, USA for contributions to development of SiC power devices

Robert Weikle, University of Virginia-Charlottesville Charlottesville, VA, USA for contributions to millimeter-wave and submillimeter-wave electronics and instrumentation for terahertz frequencies

Shien-yang Wu, Taiwan Semiconductor Manufacturing Company, Limited Hsinchu, Taiwan for leadership in CMOS process integration

Huikai Xie, University of Florida Gainesville, FL, USA for contributions to micro-electromechanical optical scanning systems

Jianbin Xu, Chinese University of Hong Kong Shatin NT, Hong Kong for contributions to nanoscale electronic materials and devices